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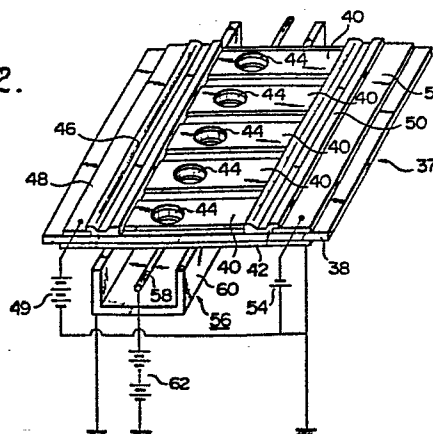
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54 Ion flow modulator.

57 An ion flow modulator with high reliability used in a photocopying machine to obtain a high quality image. The ion flow modulator (37) includes an insulating substrate (38), a common electrode (42) formed on one major surface of the insulating substrate (38), a plurality of ion flow control electrodes (40) formed on the other major surface of the insulating substrate (38), a photoconductive layer (46) formed on the insulating substrate (38) and connected to one end of each of the ion flow control electrodes (40), a first voltage application electrode (48) formed on the insulating substrate (38) and connected to the photoconductive layer (46), a resistance layer (50) formed on the insulating substrate (38) and connected to the other end of each of the ion flow control electrodes (40) so as to interpose the photoconductive layer (46) and the resistance layer (50), a second voltage application electrode (52) formed on the insulating substrate and connected to the resistance layer (50), and a DC power source (49, 54) for applying voltages having opposing polarities to the first and second voltage application electrodes (48, 52). The ion flow passage holes (44) are formed through the insulating sub-

strate (38) and the common electrode (42). A means is provided for generating ions to pass through the ion flow passage holes.

FIG 2.





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EUROPEAN SEARCH REPORT

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DOCUMENTS CONSIDERED TO BE RELEVANT			
Category	Citation of document with indication, where appropriate, of relevant passages	Relevant to claim	CLASSIFICATION OF THE APPLICATION (Int. Cl.4)
A	DE - A1 - 2 654 563 (BATELLE) * Totality * --	1,2,4,5	G 03 G 15/044
A	US - A - 4 155 093 (FOTLAND) * Fig. 2,4,6,9; abstract; claims * --	1,2,4,5	
A	DE - B - 1 522 582 (KODAK) * Fig. 1,2,4,8; claims * --	1,2,4,5	
A	US - A - 3 623 122 (FOTLAND) * Fig. 3,8 * ----	1,4,5	
			TECHNICAL FIELDS SEARCHED (Int. Cl.4)
			G 03 G 15/00
The present search report has been drawn up for all claims			
Place of search VIENNA		Date of completion of the search 27-06-1985	Examiner KRAL
CATEGORY OF CITED DOCUMENTS			
X : particularly relevant if taken alone Y : particularly relevant if combined with another document of the same category A : technological background O : non-written disclosure P : intermediate document		T : theory or principle underlying the invention E : earlier patent document, but published on, or after the filing date D : document cited in the application L : document cited for other reasons & : member of the same patent family, corresponding document	